

# **EUV Mask Handling, Chucking, & Standards Workshop**

Antwerp Hilton, Antwerpen, Belgium

October 03, 2003

Scott Hector and Thomas White, co-chairs

# Introduction & Agenda

|       |   |  |
|-------|---|--|
| 7:00  | Breakfast & registration  |  |
| 8:00  | Introduction  |  |
| 8:15  | SEMI Standards status   | S. Hector (ISMT/Motorola)              |
| 8:55  | North America development update / working groups                               | T. White (ISMT/AMD)                    |
| 9:20  | Europe development update   | C. Holfeld (AMTC/IFX)                  |
| 9:40  | Japan development update  | I. Nishiyama (ASET)                    |
| 10:00 | break   |  |
| 10:15 | LLNL flatness work  | C. Walton (LLNL)                       |
| 10:35 | Schott Lithotec   | L. Aschke (Schott Lithotec)            |
| 10:55 | Zygo - flatness metrology / handling  | R. Eandi (Zygo)                        |
| 11:15 | Nikon   | M. Sogard (Nikon)                      |
| 11:35 | ASML  | H. Meijer (ASML)                       |
| 11:55 | Morning wrap-up   | Hector / White                         |
| 12:00 | lunch   |  |
| 1:00  | International SEMATECH North  | K. Kemp (ISMT/Motorola)                |
| 1:20  | Fraunhofer - effect of humidity on chucking                                     | G. Kalkowski (Fraunhofer-IOF)          |
| 1:40  | Etec ( <b>agenda change</b> )   | T. White for M. Gesley (Etec)          |
| 2:00  | IBM carrier study   | T. White for K. Racette (IBM)          |
| 2:20  | SEMI P10 Mask Ordering  | S. Hector                              |
| 2:40  | Mask fiducials  | T. White                               |
| 3:00  | break   |  |
| 3:15  | (open / time cushion)   |  |
| 3:35  | Mask substrate thickness optimization   | T. White for R. Englestad (UWisconsin) |
| 3:55  | Discussion session: substrate thickness, fiducial marks,<br>carrier white paper |  |
| 4:45  | Afternoon/day wrapup  | Hector / White                         |
| 5:00  | Adjourn   |  |
| 5:15  | ISMT member company caucus  |  |